

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

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Title of Invention	HIGH PRESSURE PROCESSING CHAMBER FOR SEMICONDUCTOR SUBSTRATE		
Application Number :	09/912844		
Confirmation Number:	5915		
First Named Applicant:	Maximilian Biberger		
Attorney Docket Number:			
Art Unit:			
Examiner:			
Search string:	(3681171 or 4827867 or 5009738 or 6221781 or 6306564 or 6497239 or 20030005948).pn		
<u>Certification:</u> This Information Disclosure Statement was submitted under the following conditions, which satisfies the requirement under 37 CFR 1.97(e). The filer certified:			
That each item of information contained in the information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the information disclosure statement.			
US Patent Documents			
Note: Applicant is not required to submit a paper copy of cited US Patent Documents			
init	Cite.No.	Patent No.	Date
	1	3681171	1972-08-01
	2	4827867	1989-05-09
	3	5009738	1991-04-23
	4	6221781	2001-04-24
	5	6306564	2001-10-23
	6	6497239	2002-12-24
US Published Applications			
Note: Applicant is not required to submit a paper copy of cited US Published Applications			
init	Cite.No.	Pub. No.	Date
	1	20030005948	2003-01-09
Signature			

Examiner Name	Date